

Title (en)

FLUX, AND METHOD FOR THE REDUCTION OF OXIDE LAYERS ON METALLIC SURFACES

Title (de)

FLUSSMITTEL UND VERFAHREN ZUR REDUZIERUNG VON OXIDSCHICHTEN AUF METALLISCHEN OBERFLÄCHEN

Title (fr)

FONDANT ET PROCÉDÉ POUR RÉDUIRE DES COUCHES D'OXYDE SUR DES SURFACES MÉTALLIQUES

Publication

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Application

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Priority

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Abstract (en)

[origin: WO2008011933A2] The invention relates to a flux for application to and the reduction of oxide layers on a metallic solid or molten surface that is composed at least of potassium, fluoride, and moieties of water. The flux is formed from a reactant containing moieties of zirconium fluoride and/or lithium fluoride and/or sodium silicon fluoride and/or potassium cryolite and/or potassium aluminum fluoride ( $\text{KAlF}_4$ ) as well as moieties of salts based on zirconium and/or lithium and/or potassium and/or sodium and/or bismuth and/or boron and/or titanium. The invention further relates to a method for casting basic aluminum alloys as well as the use of the disclosed flux for reducing oxide layers on molten basic aluminum alloys.

IPC 8 full level

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